Reply to Office Action

Application No. 10/660,687

AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application.

- 1. (Currently Amended) A system for planarizing or polishing a composite substrate comprising (i) a polishing composition comprising (a) about 0.5 wt.% or more to about 10 wt.% of a source of fluoride ions, (b) about 1 wt.% or more to about 10 wt.% of an amine, (c) about 0.1 wt.% or more of a base, and (d) water, and (ii) an abrasive.
 - 2. (Original) The system of claim 1, wherein the system has a pH of about 7-14.
- 3. (Original) The system of claim 1, wherein the abrasive is selected from the group consisting of alumina, silica, titania, ceria, zirconia, germania, magnesia, coformed products thereof, and mixtures thereof.
 - 4. (Original) The system of claim 3, wherein the abrasive is silica.
- 5. (Original) The system of claim 1, wherein the abrasive is present in the polishing composition in a concentration of about 0.1 wt.% or more.
- 6. (Original) The system of claim 1, wherein the abrasive is fixed in or on a polishing pad.
- 7. (Original) The system of claim 1, wherein the fluoride ions are from a source of fluoride ions selected from the group consisting of fluoride salts, fluoride acids, fluoride metal complexes, and combinations thereof.
 - 8. (Original) The system of claim 1, wherein the amine is an amino alcohol.
- 9. (Original) The system of claim 8, wherein the amine is 2-dimethylamino-2-methyl-1-propanol.
- 10. (Original) The system of claim 1, wherein the base is selected from the group consisting of inorganic hydroxide bases and carbonate bases.

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- 11. (Original) The system of claim 10, wherein the base is selected from the group consisting of potassium hydroxide, sodium hydroxide, ammonium hydroxide, cesium hydroxide, sodium carbonate, and mixtures thereof.
- 12. (Original) The system of claim 1, wherein the system further comprises a quaternary ammonium compound.
- 13. (Original) The system of claim 1, wherein the system has a polishing selectivity of oxide:nitride of about 2:1 or more.
- 14. (Original) The system of claim 1, wherein the system comprises a cationic species that reduces nitride removal from the composite substrate.
- 15. (Original) The system of claim 1, wherein the fluoride ions comprise less than about 100% active fluoride ions.
- 16. (Original) The system of claim 1, wherein the system has a free alkalinity value of about 0.001-0.15 mol/l.
- 17. (Original) The system of claim 1, wherein the system has a total alkalinity value of about 0.005-0.2 mol/l.

18-42. (Canceled)